# The future of electronics and its impact on vertex detectors

## an overview of the DRD7 research program

Angelo Rivetti on behalf of the DRD7 steering committee

## **Outline**

- Relevant trends in microelectronics
- Opportunities and challenges for HEP applications
- An overview of the DRD7 R&D program

# Relevant trends in microelectronics: the IRDS 2022 roadmap



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#### IRDS<sup>™</sup> Roadmap

International Roadmap for Devices and Systems (IRDS™)



INTERNATIONAL ROADMAP FOR DEVICES AND SYSTEMS

• NTRS => ITRS => IRDS

## The key IRDS 2022 chapters

- Application Benchmarking
- Systems and Architectures
- Outside System Connectivity
- More Moore
- Beyond CMOS
- Cryogenic Electronics and Quantum
  Information Processing
- Packaging Integration
- Factory Integration
- Lithography
- Yield Enhancement
- Metrology

- Environment, Safety, Health, and Sustainability
- More than Moore
- Autonomous Machine Computing
- Mass Data Storage and Nonvolatile Memory
- Medical Devices Market Drivers
- Automotive Market Drivers

Radiation hardness not in the menu

## **Technology nodes**

	2016	2017	2018	2019	2020	2021	2022
Intel	14nm+	10nn (limited 14nm++	n i)	10nm	10nm+	10nm++	7nm EUV
Samsung	10nm		8nm	7nm EUV 6nm EUV	18nm FDSOI 5nm	4nm	3nm GAA
тѕмс	10nm	12nm	7nm n	7nm+ EUV	5nm 6nm	5nm+	4nm 3nm
GlobalFoundries		<b>2</b> F	2nm 12nm DSOI finFET		12nm 22 FDSOI FI	nm+ DSOI 12nm+ finFET	
SMIC				14nm finFET	12nm finFET	<b>8-1</b>	0nm <sub>FET</sub>
имс		14nm finFET			22nm planar		

#### Logic/Foundry Process Roadmaps (for Volume Production)

Note: What defines a process "generation" and the start of "volume" production varies from company to company, and may be influenced by marketing embelishments, so these points of transition should only be seen as very general guidelines.

Sources: Companies, conference reports and IC Insights

*Figure ES13 Scaling progressing unabated with EUV technology* 

## The gate length is not the full story



• Source: IRDS ES, p. 28

## More Moore and more than Moore

- More Moore
  - Keeping the pace with More's law when 2D ICs hits the physics (or economics) barrier
  - In practice in the mid-near term: going 3D
  - Already common for high bandwidth memories, soon to become standard also for logic
  - 3D VLSI expected to extend Moore's law up to 2040
- More than Moore
  - Heterogeneous integration
  - Use of silicon-based technology to integrate different functionalities (RF, power, sensor, actuators) into compact and high performance systems

	5	27	640	66/5
niplets	394	133	5	CP/c
ection	0.9	N/A	0.8	Tb/s/mm
BILY	0.0	3.0	1.0	TD/S/MM-

A 220GOPS 96-Core Processor with 6 Chiplets

2.3

2 · · · · · · · · · · · · · · · · · · ·	1.2	44.0	10.2	
Propagation speed	4.8	2.9	0.6	
Energy / bit / mm	0.29	0.15	0.52	

#### **ISSCC 2020@IEEE**



## **More than Moore**

• ISCAS 2022

## A 0.7 $\mu$ m-Pitch 108 Mpixel Nonacell-Based CMOS Image Sensor with Decision-Feedback Technique

Jaehoon Jun, Haneol Seo, Hyukbin Kwon, Jongyeon Lee, Beomsoo Yoon, Youngwoo Lee, Yongbin Kim, Woong Joo, Jesuk Lee, and Kyoungmin Koh System LSI Division, Samsung Electronics Hwaseong, South Korea E-mail: jaehoon.jun@samsung.com



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## **More than Moore**

This article has been accepted for inclusion in a future issue of this journal. Content is final as presented, with the exception of pagination.

IEEE JOURNAL OF SOLID-STATE CIRCUITS

### A Three-Wafer-Stacked Hybrid 15-MPixel CIS + 1-MPixel EVS With 4.6-GEvent/s Readout, In-Pixel TDC, and On-Chip ISP and ESP Function

Menghan Guo<sup>®</sup>, Shoushun Chen, Senior Member, IEEE, Zhe Gao, Wenlei Yang, Peter Bartkovjak, Qing Qin, Xiaoqin Hu, Dahai Zhou<sup>®</sup>, Qiping Huang, Masayuki Uchiyama, Yoshiharu Kudo, Shimpei Fukuoka, Chengcheng Xu, Hiroaki Ebihara, Xueqing Wang, Peiwen Jiang, Bo Jiang, Bo Mu, Huan Chen, Jason Yang, T. J. Dai, and Andreas Suess<sup>®</sup>, Member, IEEE





IEEE JOURNAL OF SOLID-STATE CIRCUITS, VOL. 58, NO. 10, OCTOBER 2023

#### A 14b 500 MS/s Single-Channel Pipelined-SAR ADC With Reference Ripple Mitigation Techniques and Adaptively Biased Floating Inverter Amplifier

Wenning Jiang, Member, IEEE, Yan Zhu<sup>®</sup>, Senior Member, IEEE, Chixiao Chen<sup>®</sup>, Member, IEEE, Hao Xu<sup>®</sup>, Member, IEEE, Qi Liu<sup>®</sup>, Member, IEEE, Ming Liu, Fellow, IEEE, Rui P. Martins<sup>(D)</sup>, *Fellow, IEEE*, and Chi-Hang Chan<sup>(D)</sup>, *Senior Member, IEEE* 

TABLE II

ADC PERFORMANCE SUMMARY AND COMPARISON

141111111111111111111111111111111111111	0,	This work	JSSC'22 J. Lagos	ISSCC'17 H. Huang	JSSC'18 E. Martens	JSSC'22 X. Guo	JSSC'18 R. Sehga
	Architecture -	- PROCOSAR	OPIpe-SAR67	dERi <mark>\$ED\$AR</mark> Od	<sup>B</sup> Pipe-SAR	Pipe-SAR	Pipelined
	Technology -50	28nm	16nm	65nm	16nm	40nm	28nm
ADC core	Sample Rete[MS/s]	500 မီုတို	500	3 330	<b>300</b> ₿2x TI)	625	280
	Resolution [bit]	14 14	11.5		13.5	13	12
Dum — 🔶	Supply [V] _150	1/1:2	<b>0</b> .9	1.3 <sup>17</sup>	0.8	1.15	1
7b SAR	Input Swing [V] <sup>0</sup>	1.6 <sup>1</sup>	0.28 Normalized Er	0.3 2.4	<sup>0.4</sup> N/A <sup>0.5</sup>	2.2	1.2
C&RRN 🛓 🎽	SFDR @Nyq.[dB]	80.55	75.5	75.8	73.6	70	77
	SNDR @Nyq.[dB]	64.2	62.3	63.5	64	62.4	64
	Power[mW]	6.34	3.3	6.2	3.6	7.05	13
ge 2	FoM <sub>w</sub> @N <mark>y</mark> g,[f <b>b/i∂×</b> s}}	DNL)= <mark>M</mark> ax(DN	RRN_0 <b>6_}2</b> Max(E	NLRRN504)	9.2	10.5	35.8
SAR 🗸	FoMs@Ny4[6B]	170.2	171.1	167.8	170.2	168.9	164.3
	Referenc	789	No	No	No -	Yes	No
	Decap on Ref [pF]	3	105	NPA		N/A	N/A
	Core Areadingm <sup>2</sup> ]	0.018*	0.0404*	0.08	0.11*	0.022	0.22
9.3dB, SFDR=50.4dB	Ripple Mitigation	<sup>4</sup> RRC/RRN <sub>F</sub>	BOTOBLASION	rent [mA	Aux. DAC	No	No
3.7dB, SFDR=80dB	-* Core area w/ refere	nce decap					



RRC ON, RRN OFF: SNDR=6

.....bao.....



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### A 13b 600-675MS/s Tri-State Pipelined-SAR ADC With Inverter-Based Open-Loop

## RA1 Dig.-S. CDAC2 Others Residue Amplifier $[nV^2]$ $[nV^2]$ $[nV^2]$ $[nV^2]$

[nV<sup>2</sup>] [nV<sup>2</sup>] [nV<sup>2</sup>] Xiaofeng Guo<sup>®</sup>, Member, IEEE, Run Chen, Senior Member, IEEE, Zhenqi Chen, Senior Member, IEEE, and Bin Li, Member, IEEE

	30.53	18.25	2.85	0.97
, D	35.1%	21.0%	3.3%	1.0%



		This Work	ISSCC 2021 [6]	JSSC 2017 [5]	JSSC 2020 [1]	VLSI 2021 [11]	ISSCC 2022 [10]
Archited	cture	3-Stage Pipe-SAR	2-Stage Pipe-SAR&TI DSM	2-Stage Pipe-SAR	3-Stage Pipe-SAR	2-Stage Pipe-SAR	2-Stage Pipe-SAR
SAR Archi	itecture	Tri-State	Binary	Binary	Binary	Binary	Binary
RA Architecture		Open Loop Inverter-Based	Open Loop Source-Follower	en Loop Open Loop Open Loop :e-Follower Gm-C + V2T Gm-R		Closed Loop Ring-Amp	Closed Loop
Techno	Technology 40		7nm	65nm	28nm	16nm	28nm
Measured S	Samples	10	5	2	1	1	1
Supply Vol	tage [V]	1.1 ~ 1.2	0.77 ~ 0.9	1.25 ~ 1.35	1	0.8 ~ 1	1.1
Measured Tem	perature [°C]	-40 ~ 125	-40 ~ 80	-5 ~ 85	0 ~ 80	-	-
Resolutio	n [bits]	13	12	12	12	11.5	14
Fs [MS	6/s]	625 (ups to 675)	600	330	1000	500	130
Input Swin	Input Swing [Vpp]		1	2.4	1.2	1.8	-
DR [d	IB]	67	-	-	-	63.6	-
	ariation [dP]	59.8~62.8 (Mean)	> 54	0.9 degradation	_	_	
SINDE W/ FVI V	anation [ub]	< 1.7 (1-σ)	~ 54	0.6 degradation	-	-	-
	LF	63.8	56.6	67.7	61.36	-	72.9
	HF	62.4	55.3	63.5	59	62.9	72.5
Peak SFD	R [dB]	76	71.1	83.4	74.5	75.5	87.5
Power [	mW]	7.05	13	6.23	7.6	2.8	0.82
FoM <sub>w</sub> @HF	[fJ/c-s]	10.5	45.6	15.4	9.28	4.9	1.8
FoM <sub>s</sub> @H	IF [dB]	168.9	158.9	167.8	168.2	172.4	181.5
Area [n	nm²]	0.022	0.037	0.08	0.009	0.0084	0.013
Cs [p	F]	0.29	0.69	1	0.54	-	1.6
Bias-Fre	e RA	Yes	No	No	No	No	No

TABLE III ADC Performance Summary and Comparison

## **Key IPS: ADCs**

#### **ISSCC 2021**

#### 10.5 A 12b 600MS/s Pipelined SAR and 2×-Interleaved Incremental Delta-Sigma ADC with Source-Follower-Based Residue-Transfer Scheme in 7nm FinFET

Seungyeob Baek, Ilhoon Jang, Michael Choi, Hyungdong Roh, Woongtaek Lim, Youngjae Cho, Jongshin Shin

Samsung Electronics, Hwasung, Korea





#### Power: 13 mW

## **Key IPs: TDCs**

IEEE TRANSACTIONS ON INSTRUMENTATION AND MEASUREMENT, VOL. 72, 2023



#### s Time-Resolution 7.5-bit Stochastic D-Digital Converter Based on Two Arbiter Groups

Clk2 Graduate Student Member, IEEE, Xinquan Lai (来新泉)<sup>®</sup>, Member, IEEE, eng Wang (王宇恒)<sup>®</sup>, Graduate Student Member, IEEE



		[2]	[19]	[23]	[29]	[30]	[32]	This work
Architecture		multi-level	multi- segment	pipeline	stochastic phase interpolation	stochastic phase interpolation	stochastic	stochastic
Technology	/ [nm]	180	180 65 14 180 6		65	180		
Sampling rate	e [MHz]	333	0.82	250	100	60	100	50
Time resolut	ion [ps]	50	36	1.12	1.17	63	0.36	0.55
Input range [ns]		13100	63.5	0.6	1.2	16.67	0.05	0.105
NOB [b	its]	18*	10.8	9	10	8	7	7.5
<b>x</b> • •	INL [LSB]	0.71	1.5	1.7	2.3	1.1	0.75	-1.81
Linearity	DNL [LSB]	0.47	0.65	0.6	0.8	0.8	0.77	1.87
Effective time reso	Effective time resolution [ps]**		90	3.01	3.86	132.3	0.63	1.55
Power [mW)		87.6	0.44	15.4	0.78	25	6.2†	19.8
Area [mm <sup>2</sup> ]		2.25	0.11	0.14	0.036	1.13	0.068	0.893
FoM [pJ.ps/co	onvstep]	257.22***	27.09	0.36	0.029	215.33	0.305	3.38



TABLE I Performance Summary and Comparison

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### Silicon Photonics Transmitter Iodulator and CMOS Driver

, Jie Sun<sup>®</sup>, Jeffery Driscoll, Ranjeet Kumar<sup>®</sup>, Hasitha Jayatilleka<sup>®</sup>, *Member, IEEE*, James Jaussi, and Bryan Casper



## 28 nm + Silicon Photonics

## **IC economics**

Hardware Design Cost



- 1.5 billions cell phones/year
- 250 millions wafers/year

# Chiplets, again





How a future vertex detectors could look like:

- An active support (stitched sensing layers ( with internal gain) and bare minimum electronics
- Efficient digital processing layer (28 nm or beyond)

Key aspects:

• Efficient data and power management, smart and flexible digital readout, fast data transfer, access to critical technologies, radiation hardness...

## **Opportunities and challenges**

- IC technologies deploy fantastic capabilities
- Moore law expected to continue in the foreseeable future within an evolutionary paradigm with 3D stacking becoming more and more prominent
- We do not fully exploit in electronics for HEP what technology can offer even today
  - Small design teams
  - Low production volumes
  - Long development cycles
  - Lack of shared, reusable IPs
  - Lack of appropriate simulation/verification environments
  - Difficulties in securing experienced people
  - Budgets
  - ....
- Can we address some of these issue?

## **DRD7** collaboration

- DRD7 in a nutshell: a collaborative effort to push electronics for particle detectors beyond our state of the art through a set of well harmonised multinational projects
- A dynamic environment: projects can be proposed at regular times
- A structured environment: projects are framed along prioritised lines of interest (the working groups) and are expected to be transformative for the field, multinational and with reasonable resources to make the project feasible
- It's an R&D: a project could also yield a null result!

# **DRD7 working groups and projects**

#### • WG7.1: Data density and power efficiency

- Silicon photonics transceivers
- Powering next generation systems
- Wireless for data & power
- WG7.3: 4D and 5D techniques
  - High performance ADCs and TDCs
  - Calibration strategies for timing systems
  - Timing distribution systems
- WG7.5: Back-end systems and COTS
  - COTS architectures, tools and IPs
  - No back-end, full 100GbE from FE to DAQ
  - Generic back-end board

- WG7.2: Intelligence on detector
  - Programmable logic array IP
  - Radiation tolerant RISC-V processor
  - Virtual electronics prototyping
- WG7.4: Extreme environments
  - Cryogenic CMOS PDKs
  - Radiation tolerance of advanced nodes
  - Proximity cooling
- WG7.6: Complex imaging ASICs and technologies
  - Common access to selected imaging technologies and IP blocks
  - Common access to 3D advanced integration

#### • WG7: Technologies and tools

## Interface with other DRDs

- R&D in electronics is cross-boundary
- DRD7 tasks
  - Develop and maintain common IPs and subsystems, encompassing hardware, firmware and software
  - Develop common, generic complete components or system when too complex to be designed in a single DRD
  - Provision access to vendors and tools
  - Review system specifications and designs as requested
- DRDx specific projects
  - Determination of system parameters and specifications
  - Planning and costing of prototype development and productions
  - Production, verification and integration of ASICs and other project-specific components
  - Testing and operation of large scale projects

## A DRD7 project example

- WP71.b Power efficiency
  - Reduced power voltage <>> more bias current <>> heavier cables
- Project goals: improve power efficiency and reduce material budget in future detectors
- Characterisation of new HV technologies and IP developments





#### Contribution from:

- FH Dortmund
- ITAINNOVA
- UNIMI+INFN

## Introducing on chip DC-DC converters



# **On chip DC-DC IP example**

- iPOL5V
- 28 nm fully integrated DC-DC converter
- Input 5 V
- Output 0.9 V 1 V @ 500 mA
- Radiation tolerante: 1 Grad





3.2 x 2.1 mm

# **Serial powering**



- Deploying novel and more efficient shunt LDO
- Serial powering for CMOS sensors (encouraging results form ATLASPIX3

## **DRD7 status and plans**

- Two workshop held (September and March 2023)
  - https://indico.cern.ch/event/1214423/ (March 2023)
  - https://indico.cern.ch/event/1318635/ (Sept 2023)
- Letter of intent issued on September 15th, 2023
  - <u>https://indico.cern.ch/event/1318635/contributions/5551432/attachments/2720844/4726969/</u> DRD7%20Letter%20of%20IntentV2.1.pdf
  - Collaboration proposal being worked-out for end of the year

